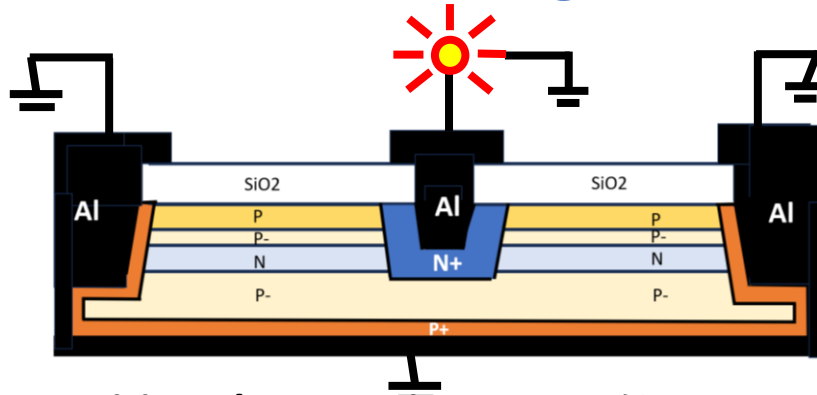
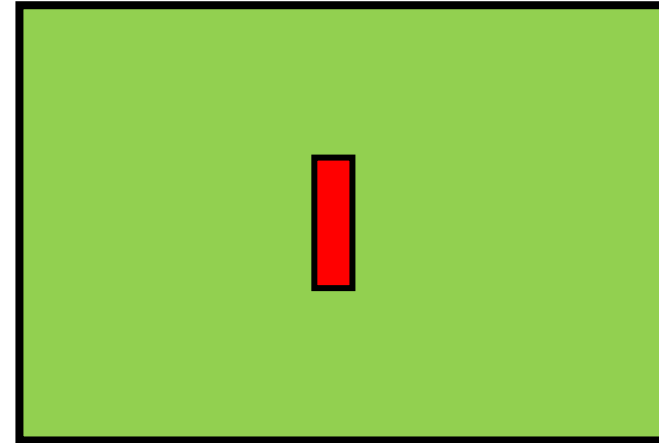


006 Mask 01 Setting for N+ Formation



Positive Photo Resist は光が照射した部分のみが溶液で解けて除去できます。



<https://lushbooklife.com/news-of-positive-photoresist/>

Metal Masking Plate 01		Metal Masking Plate 01	
Positive Photo Resist			
SiO2			
P		P	
P-		P-	
N		N	
P-		P-	